

1765
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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE



Re Application of

Jason M. Benz

Serial No.: 09/695,028

Filed: October 24, 2000

RECEIVED
JUL 03 2003
TC 1700

Group Art Unit: 1765

Examiner: Alanko, Anita K.

For: METHOD FOR THIN FILM LASER REFLECTANCE CORRELATION FOR
SUBSTRATE ETCH ENDPOINT

Honorable Commissioner of Patents
Alexandria, Virginia 22313-1450

EXCESS CLAIM FEE PAYMENT LETTER

Sir:

Transmitted herewith is an amendment in the above-identified application. The fee has been calculated and is transmitted as shown below.

	<u>AFTER AMENDMENT</u>	<u>PREV. PAID FOR</u>	<u>EXTRA CLAIMS PRESENT</u>	<u>RATE</u>	<u>FEE DUE</u>
Total Claims	42 -	36	=6	x \$18.00	\$ 108.00
Indep. Claims	3 -	3	= 0	x \$84.00	\$.00
TOTAL ADDITIONAL FEE FOR THIS AMENDMENT					\$ 108.00

Please charge Assignee's Deposit Account No. 09-0456 in the amount of \$ 108.00 to cover the excess claim fees. A duplicate copy of this sheet is enclosed. The Commissioner is authorized to charge any deficiencies in fees and credit any overpayment of fees to Assignee's Deposit Account No. 09-0456.

Respectfully Submitted,

Sean M. McGinn
Reg. No. 34,386

Date: June 30, 2003
McGinn & Gibb, PLLC
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#17/D
ua
7/7/03

AMENDMENT UNDER 37 C.F.R. §1.111

Sir:

In response to the Office Action dated April 2, 2003, please consider the following
remarks in the above-identified application:

IN THE SPECIFICATION:

Please replace the paragraph beginning on page 5, line ¹³~~18~~ with the following
paragraph.

D₁

-- Generally, the invention takes advantage of a metal film (e.g., a chrome film) which
is already on a photomask used with the etching process. For purposes hereinbelow, chrome
will be assumed to be the metal film, but of course, as would be known by one ordinarily
skilled in the art after taking the present specification, any metal (or other opaque material)
providing a predetermined reflectance signal could be used. The surface of the chrome film
contains an anti-reflective chrome oxide which isolates the chrome from the etching process.
This film is etched during the quartz etch process. By correlating the quartz etch to the rate of
the chrome oxide etch, the reflectance signal from the chrome can be used to determine an
endpoint for the quartz etch process. --